


Stanford



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The William E. Ayer Professor in Electrical Engineering, Emeritus

 Resume available Online

CONTACT INFORMATION

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ACADEMIC APPOINTMENTS

- Emeritus Faculty, Acad Council, Electrical Engineering

Teaching

STANFORD ADVISEES

Doctoral Dissertation Reader (AC)

Hongquan Li

Doctoral Dissertation Reader (NonAC)

Lars Neustock

Publications

PUBLICATIONS

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- **Laser acceleration and deflection of 96.3 keV electrons with a silicon dielectric structure** *OPTICA*
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- **Single Cell Profiling of Circulating Tumor Cells: Transcriptional Heterogeneity and Diversity from Breast Cancer Cell Lines** *PLOS ONE*
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- **Sub-15 nm Photo-electron Source Using a Nano-aperture Integrated with a Nano-antenna** *Conference on Lasers and Electro-Optics (CLEO)*
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IEEE.2011
- **Semiconductor crystal islands for three-dimensional integration** *54th International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication*
Crnogorac, F., Wong, S., Pease, R. F.
A V S AMER INST PHYSICS.2010: C6P53-C6P58
- **Optical and computed evaluation of keyhole diffractive imaging for lensless x-ray microscopy** *54th International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication*
Dai, B., Zhu, D., Jaroensri, R., Kulalert, K., Pianetta, P., Pease, R. F.
A V S AMER INST PHYSICS.2010: C6Q1-C6Q5
- **Nondestructive detection of deviation in integrated circuits** *54th International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication*
Baghaei, L., Dai, B., Pianetta, P., Pease, R. F.
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- **Pulsed laser techniques for nanographoepitaxy** *52nd International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication*
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 - **Secondary electron detection for distributed axis electron beam systems** *MICROELECTRONIC ENGINEERING*
Tanimoto, S., Pickard, D. S., Kenney, C., Pease, R. F.
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 - **Spatial Quantized Analog-to-Digital Conversion Based on Optical Beam-Steering** *JOURNAL OF LIGHTWAVE TECHNOLOGY*
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- **Alkylsiloxane self-assembled monolayer formation guided by nanoimprinted Si and SiO₂ templates** *APPLIED PHYSICS LETTERS*
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